ket No 202450US0

SEP 1 6 2003

NOV OS AUSED IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Atsushi SHIOTA, et al.

SERFAL NO: 09/770,289

GAU:

1712

FILED:

January 29, 2001

EXAMINER: M. FEELY

FOR:

PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM,

AND SEMICONDUCTOR DEVICE

REQUEST FOR EXTENSION OF TIME **UNDER 37 C.F.R. 1.136**

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

K:	
It:	is hereby requested that a one month extension of time be granted to October 9, 2003 for
	filing a response to the Official Action dated: June 9, 2003.
	responding to the requirements in the Notice of Allowability dated:
	responding to the requirements in the Notice of Allowability dated: filing the Formal Drawings. The Issue Fee due has been timely filed.
	responding to the Notice to File Missing Parts of Application dated:
	filing a Notice of Appeal. A timely response to the final rejection, due has been filed.
	Applicant claims small entity status. See 37 CFR 1.27. Therefore, the fee amount shown below is reduced by one-half.
T	he required fee of \$110.00 is enclosed herewith by check and any further charges may be made against the Attorney f Record's Deposit Account No. <u>15-0030</u> . A duplicate copy of this sheet is enclosed.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,

MAIER & NEUSTADT, P.C.

11/03/2003 DDATES

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